

Place type a plus sign (+) inside this box → (+)

PTO/SB/08A (08-09)

Approved for use through 10/31/2002. OMB 0651-0031

U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it carries a valid OMB control number.

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet 1 of 1

Complete if Known

Application Number	10/091,338
Filing Date	March 6, 2002
First Named Inventor	Toru MITSUKI et al.
Group Art Unit	2824
Examiner Name	Bradley Smith
Attorney Docket Number	0756-2448

U.S. PATENT DOCUMENTS

Examiner Initials	Cite No.	U.S. Patent Document		Name of Patent or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Paragraph or Relevant Figure Appear
		Number	Kind Code (if known)			

FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Foreign Patent Document			Name of Patent or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Paragraph or Relevant Figure Appear	1*
		Other	Number	Kind Code (if known)				
TSKS		JP	07-162004			06/23/1995		AB
		WO	93-10555			05/27/1993		AB
		JP	04-035021			02/05/1992		AB
		JP	04-286336			10/12/1992		AB

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner Initials	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	1*
TSKS		H. Koseki et al., Recent Progress of Low Temperature Poly-Si Technology, Electronic Display Forum, Pages 4-31 to 4-38 and English Translation, Pages 1-21, April 15, 1999.	14
TSKS		Kenji Sera et al., Uniformity Improvement of Excimer Laser Crystallized Poly-Si Thin Film Transistors, AM-LCD '96/IDM '96, Pages 85-88.	
TSKS		M. Bornel et al., Polycrystalline Silicon Thin-Film Transistors with Two-Step Annealing Process, IEEE Electron Device Letters, Vol. 14, No. 12, Pages 551-553, December 1993.	
TSKS		M. Fuse et al., Performance of Poly-Si Thin Film Transistors Fabricated by Excimer-Laser Annealing of SiH ₄ and Si ₂ H ₆ Source Low Pressure Vapor Deposited a-Si Films With or Without Solid-Phase Crystallization, Solid State Phenomena, Vols. 37-38, Pages 565-570, 1994.	

Examiner Signature	TSKS	Date Considered	6/15/04
--------------------	------	-----------------	---------

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.